

L Number	Hits	Search Text	DB	Time stamp
1	16613	(etch\$3 remov\$3) near3 oxide same metal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:13
2	696	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:01
3	0	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and \$5flourocarbon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:02
4	0	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and \$5flourocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:02
5	0	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and flourocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:02
6	27	((etch\$3 remov\$3) near3 oxide same metal) and polish\$3 near3 metal) and \$5fluorocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 10:18
7	5295	(etch\$3 remov\$3) near5 metal near oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 10:18
8	150	((etch\$3 remov\$3) near5 metal near oxide) and \$5fluorocarbon\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:50
9	1	etch\$3 near5 metal near oxide same ph same (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:51
10	6	etch\$3 near5 metal near oxide same ph and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:55
11	94464	etch\$3 near5 metal near oxide an ph and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:55
12	27	etch\$3 near5 metal near oxide and ph and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 11:55
13	21	(etch\$3 near5 metal near oxide and ph and (potassium near hydroxide koh)) not (etch\$3 near5 metal near oxide same ph and (potassium near hydroxide koh))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:02
14	317	438/754.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:03
15	18	438/754.ccls. and ph and etch\$3 near3 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:10
16	6	etch\$3 near (cuo copper near oxide tungsten near oxide) same ph	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:10
17	66	etch\$3 near3 oxide same metal same ph	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 12:13

-	9162	polish\$3 near4 metal and (cu copper w tungsten al aluminum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 09:00
-	1400	(polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:51
-	1177	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:51
-	984	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:52
-	68	((((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical) and (fluorocarbon\$1 hydrofluorocarbon\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/10 07:53
-	186	((((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical) and (potassium near hydroxide koh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/15 12:56
-	1	("5,527,423").PN.	USPAT	2003/07/10 09:56
-	9	("5478436" "5482174" "5645737" "5830280" "5972862" "6043206" "6090214" "6162301" "6171405").PN.	USPAT	2003/07/10 09:25
-	22	("4370173" "4376673" "4871422" "5200024" "5286300" "5354712" "5382296" "5630904" "5662769" "5700383" "5705089" "5714203" "5794299" "5806126" "5810938" "5824601" "5895563" "5897375" "5954997" "5965036" "5972862" "5981454").PN.	USPAT	2003/07/10 09:27
-	14	("4879258" "4960485" "5196353" "5314843" "5514245" "5730642" "5775980" "5837557" "5859466" "5934980" "5957750" "6020262" "6120347" "6150271").PN.	USPAT	2003/07/10 09:41
-	2745	438/691-693,695,722,723,724.ccls.	USPAT	2003/07/10 09:57
-	209	((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and 438/691-693,695,722,723,724.ccls.	USPAT	2003/07/10 09:57
-	145	((((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and 438/691-693,695,722,723,724.ccls.) not (((polish\$3 near4 metal and (cu copper w tungsten al aluminum)) and (remov\$3 clean\$3 etch\$3) near4 oxide) and semiconductor) and chemical near mechanical) and (potassium near hydroxide koh))	USPAT	2003/07/10 09:58
-	13	((("6383934") or ("5934980") or ("6162301") or ("6265781") or ("5981454") or ("6546939") or ("6432825") or ("6464568") or ("5482174") or ("6171405") or ("5954997") or ("5934980") or ("5806126") or ("5830280")).PN.	USPAT	2003/09/15 12:57